

제23회 한국반도체학술대회

2016년 2월 22일(월)-24일(수), 강원도 하이원리조트

D. Thin Film Process Technology 분과

Room B

태백II+III(5층)

2016년 2월 23일(화) 15:10-17:10

[TB3-D] Process Technology for Thin Films

좌장 : 이상운(아주대학교), 최리노(인하대학교)

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| TB3-D-1 | 15:10-15:25 | Post Etch/Strip Low-k Recovery for 64nm Pitch and Below: A Easy and Feasible Way for RC Gain and Reliability Improvement
Thomas Ozinda, Tae-Jin Yim, Jongmin Baek, SangHoon Ahn, Byunghee Kim, Nae-in Lee, Siyoung Choi, Ho-kyu Kang, and ES Jung
<i>Semiconductor R&D Center, Samsung Electronics Co. Ltd.</i> |
| TB3-D-2 | 15:25-15:40 | Ultrathin ZnS Interfacial Passivation Layer for HfO₂ on InP Substrate
Seung Hyun Kim ¹ , Hyun Soo Jin ² , Dae Hyun Kim ¹ , Tae Jun Seok ² , Yoo Jin Cho ¹ , and Tae Joo Park ^{1,2}
¹ <i>Department of Advanced Materials Engineering, Hanyang University,</i>
² <i>Department of Materials Science & Chemical Engineering, Hanyang University</i> |
| TB3-D-3 | 15:40-15:55 | Process Temperature Dependence on the Effective Work Function in the MOS Device with PEALD TiN using TDMAT Source
Youngjin Kim, Donghwan Lim, Hoon Hee Han, and Changhwan Choi
<i>Division of Material Science and Engineering, Hanyang University</i> |
| TB3-D-4 | 15:55-16:10 | Atomic Layer Deposition of Ru Thin Film and Its Application to a Capacitor Electrode
Cheol Hyun An ¹ , Woongkyu Lee ¹ , Min Jung Chung ¹ , Sang Hyeon Kim ¹ , Lansalot Clement ² , and Cheol Seong Hwang ¹
¹ <i>Department of Materials Science and Engineering and Inter-university Semiconductor Research Center, Seoul National University,</i>
² <i>Air Liquide Laboratories Korea</i> |
| TB3-D-5 | 16:10-16:25 | Phase Transformation Studies of Al₂O₃ and Al₂O₃-SiO₂ Thin Films
Jae Kyu Choi, Jinho Bin, Ilyoung Kwon, Se-Aug Jang, Sang-Deok Kim, and Noh-Jung Kwak
<i>R&D Division, SK hynix Inc.</i> |
| TB3-D-6 | 16:25-16:40 | Interface Sulfur Passivation with H₂S Pre- and Post-deposition Annealing for Atomic-layer-deposited HfO₂ Film on InP
Hyun Soo Jin ¹ , Tae Jun Seok ¹ , Seung Hyun Kim ² , Yoo Jin Cho ² , Deok-Yong Cho ³ , and Tae Joo Park ^{1,2}
¹ <i>Department of Materials Science & Chemical Engineering, Hanyang University,</i> ² <i>Department of Advanced Materials Engineering, Hanyang University,</i> ³ <i>IPIT and Department of Physics, Chonbuk National</i> |

The 23rd Korean Conference on Semiconductors (KCS 2016)

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